



- (51) International Patent Classification:
B24B 37/24 (2012.01)
- (21) International Application Number:
PCT/US2014/047065
- (22) International Filing Date:
17 July 2014 (17.07.2014)
- (25) Filing Language: English
- (26) Publication Language: English
- (30) Priority Data:
13/955,398 31 July 2013 (31.07.2013) US
- (71) Applicant: NEXPLANAR CORPORATION [US/US];
7175 NW Evergreen Parkway, Suite 200, Hillsboro, Ore-
gon 97124 (US).
- (72) Inventors: HUANG, Ping; 1765 NW 173rd Avenue, Apt.
703, Beaverton, Oregon 97006 (US). ALLISON, William
C.; 4243 NW Chaparral Terrace, Beaverton, Oregon 97006
(US). FRENTZEL, Richard; 31900 Serrento Drive, Mur-
rieta, California 92563 (US). LEFEVRE, Paul Andre;
3926 NW Sunset Circle, Portland, Oregon 97229 (US).
KERPRICH, Robert; 14788 NW Jewell Lane, Portland,
Oregon 97229 (US). SCOTT, Diane; 3140 NE Bryce
Street, Portland, Oregon 97212 (US).
- (74) Agents: BERNADICOU, Michael A. et al.; Blakely
Sokoloff Taylor Zafman LLP, 1279 Oakmead Parkway,
Sunnyvale, California 94085 (US).
- (81) Designated States (*unless otherwise indicated, for every
kind of national protection available*): AE, AG, AL, AM,
AO, AT, AU, AZ, BA, BB, BG, BH, BN, BR, BW, BY,
BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM,
DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT,
HN, HR, HU, ID, IL, IN, IR, IS, JP, KE, KG, KN, KP, KR,
KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME,
MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ,
OM, PA, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SA,
SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM,
TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM,
ZW.

[Continued on next page]

(54) Title: LOW DENSITY POLISHING PAD

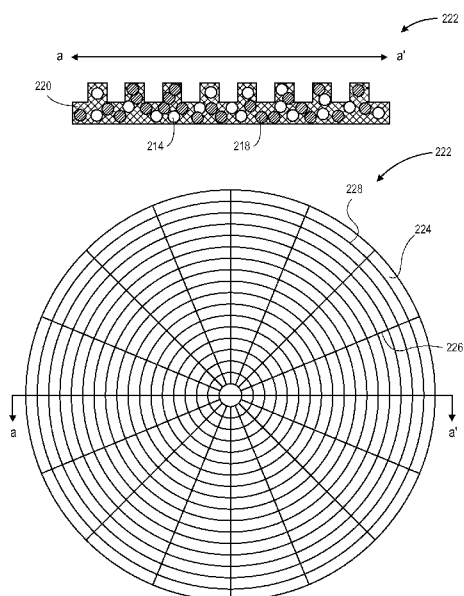


FIG. 2G

(57) Abstract: Low density polishing pads and methods of fabricating low density polishing pads are described. In an example, a polishing pad for polishing a substrate includes a polishing body (222) having a density of less than 0.5 g/cc and composed of a thermoset polyurethane material (220). A plurality of closed cell pores (214, 218) is dispersed in the thermoset polyurethane material (220).



(84) Designated States (*unless otherwise indicated, for every kind of regional protection available*): ARIPO (BW, GH, GM, KE, LR, LS, MW, MZ, NA, RW, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK,

SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, KM, ML, MR, NE, SN, TD, TG).

Published:

— *with international search report (Art. 21(3))*